



Description

Trichlorosilane (SiHCl_3) is a chlorosilane which is formed by the reaction of metallurgical grade silicon (Si) with Hydrogen (H_2) and Silicon Tetrachloride (SiCl_4).

Applications

High purity Trichlorosilane is the most important raw material for the production of solar silicon. It is widely used in the growth of epitaxial and polycrystalline silicon in a Chemical Vapour Deposition (CVD) reactor.

Product Specifications

Analysis	Specification	Analytical Method
Purity	> 99,7 %	Gas Chromatography
Dichlorosilane (SiH_2Cl_2)	< 0,15 %	Gas Chromatography
Silicon Tetrachloride (SiCl_4)	< 0,15 %	Gas Chromatography
Boron (B)	< 10 ppbw	ICP - MS
Phosphorous (P)	< 50 ppbw	ICP - MS
Iron (Fe)	< 10 ppbw	ICP - MS
Carbon (C)	< 500 ppbw	I.R

Shipping Information

Cylinder	ISO Container (17.500 litres tank)
Discharge location	Top
Working pressure	4 bar
Test pressure	6 bar
DOT Trichlorosilane	TCS (SiHCl_3)
Hazard Class	4.3
ID No	UN 1295
DOT Label	Dangerous when wet, flammable liquid, corrosive
CAS No	10025 - 78 - 2
Shipped as	Liquefied gas



We produce, sell and distribute worldwide Trichlorosilane (SiHCl_3) and Polycrystalline Silicon

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Information disclosed in this document has been prepared according to present knowledge and experience. The information herein is accurate within the limits of the analytical methods employed. Siliken Chemicals reserves the right of making any changes according to further developments. This information is provided with the understanding that any use of the information is at the sole discretion, responsibility and risk of the Customer.



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